Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claim 1-7 (canceled)

8. (currently amended) An apparatus for fabricating a III-V nitride film including at least Al on a given substrate using a Hydride Vapor Phase Epitaxy method using a chloride-based gas, comprising a double reactor structure constructed of an inner reactor to hold a substrate and at least an aluminum metallic material therein and an outer reactor surrounding the inner reactor comprising a silicon oxide-based material, the inner reactor and the outer reactor being spaced from one another, and an evacuation system in communication with a space between the inner reactor and the outer reactor ~~being evacuated and maintained in~~ vacuum, a gas-supplying means to introduce chloride-based gas, ammonia gas and carrier gas into the inner reactor, a heater to heat the interior of the inner reactor, and a gas leak-detecting means with a gas concentration sensor to detect gas leaks between the inner reactor and the outer reactor.

9. (previously presented) A fabricating apparatus as defined in claim 8, further comprising means for generating a given pressure difference between the inner reactor and the outer reactor, and means for detecting a given gas concentration in either the inner reactor or the outer reactor which is lower in pressure, said means for detecting said given gas concentration comprising a gas concentration sensor.

10. (previously presented) A fabricating apparatus as defined in claim 9, wherein said means for generating a given pressure sets the interior pressure of the outer reactor to be lower than that of the inner reactor, and said gas concentration sensor is set to detect said given gas concentration in the outer reactor.

11. (previously presented) A fabricating apparatus as defined in any one of claims 8-10, wherein the gas concentration sensor comprises at least one selected from the group consisting of an ammonia gas sensor, a hydrogen chloride gas sensor and an inert gas sensor.

Claims 12-19 (canceled)